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FORM PTO-1449  INFORMATION DISCLOSURE STATEMENT	ATTY. DOCKET 033035 M 0341	SERIAL NO. 10/691,540
	APPLICANTS: Kensaku MO	TOKI, et al.
	FILING DATE	GROUP ART UNIT
	October 24, 2003	1722
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EXAMINER:	(3.0.11		DATE CONSIDERED:	
/Matthew Song/		new Song/	11/08/2007	

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.